

S/N TBD
Docket: CS03 - 039
Group art unit : ___ TBD

Date 11/21/2003

**To: Commissioner of Patents and Trademarks
P.O. Box 1450 Alexandria, VA 22313-1450**

**Fr: William J. Stoffel Reg. No. 39,390 Cust No. 30402
PMB 455
1735 Market St - Suite A
Philadelphia, PA 19103**

Subject:

Serial No. TDB
Docket CS03 - 039
File Date: with application
Inventor: Chen

**title: CMP Polishing Heads Retaining Ring Groove
Design for Microscratch Reduction**

Group art unit: TBD

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO A820 (also PTO-1449), Information
Disclosure Citation and references.

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the
United States Postal Service as first class mail in an envelope addressed
to: Commissioner for Patents, P.O. Box 1450 Alexandria, VA 22313-1450, on
Nov 24, 2003.

Signature/Date

William J. Stoffel
William J. Stoffel Reg. No. 39,390
Customer number 30402

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The following Patents and/or Publication are submitted to
comply with the duty to disclose under CFR 1.97-1.99 and 37
CFR 1.56.

US 6,386,962B1(Gotkis et al.) that shows a wafer carrier
with retainer ring for a chemical-mechanical polish (CMP)
apparatus.

US 6,527,624 B1(Tollers et al.) shows a retaining ring.

US 6,110,025(Williams et al.) teaches a retainer ring
with passages.

US 6,293,850 B1(Lin et al.) shows retaining ring with
slurry passages at the bottom of the retainer ring.

US 6,224,472 B1(Lai et al.) teaches a retaining ring with
channels.

Sincerely,

with [Signature]

William J. Stoffel
Reg. No. 39,390
Customer number 30,402

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| INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i> | Docket Number (Optional) cs03-039 | Application Number |
| | Applicant(s) chen et | |
| | Filing Date | Group Art Unit |

U.S. PATENT DOCUMENTS

| *EXAMINER INITIAL | REF | DOCUMENT NUMBER | DATE | NAME | CLASS | SUBCLASS | FILING DATE IF APPROPRIATE |
|----------------------|-----|-----------------|------|------------------|-------|----------|-------------------------------|
| | | US 6,386,962B1 | | (Gotkis et al.) | | | |
| | | US 6,527,624 B1 | | Tollers et al.) | | | |
| | | US 6,110,025 | | Williams et al.) | | | |
| | | US 6,293,850 B1 | | Lin et al.) | | | |
| | | US 6,224,472 B1 | | Lai et al. | | | |
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FOREIGN PATENT DOCUMENTS

| REF | DOCUMENT NUMBER | DATE | COUNTRY | CLASS | SUBCLASS | Translation | |
|-----|-----------------|------|---------|-------|----------|-------------|----|
| | | | | | | YES | NO |
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OTHER DOCUMENTS *(Including Author, Title, Date, Pertinent Pages, Etc.)*

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| EXAMINER | DATE CONSIDERED |
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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.